

SEMICONDUCTOR FABRICATING APPARATUS

5

ABSTRACT OF THE DISCLOSURE

10 A resonant frequency sensor is disposed in a plasma-
processing chamber included in a semiconductor
fabricating apparatus. A change in the resonant
frequency caused by etching, sputtering or deposition is
sensed in order to detect the timing of performing the
maintenance of the processing chamber. If data
representing the relationship between an amount of
15 etching or deposition occurring at a predetermined
position in the processing chamber and occurrence of an
abnormality is produced in advance, an optimal
maintenance timing can be determined.